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CLAIMS

The following is a copy of Applicant's claims that identifies language being added with underlining ("___") and language being deleted with strikethrough ("——"), as is applicable:

- (Previously Presented) A polymer_composition, comprising:
 a photodefinable polymer including a sacrificial polymer and a photoinitiator.
- 2. (Previously Presented) The polymer composition of claim 1, wherein the photoinitiator is a negative tone photoinitiator.
- 3. (Previously Presented) The polymer composition of claim 1, wherein the photoinitiator is a positive tone photoinitiator.
- 4. (Previously Presented) The polymer composition of claim 1, wherein the sacrificial polymer is selected from polynorbornenes, polycarbonates, polyethers, polyesters, functionalized compounds of each, and combinations thereof.
- 5. (Previously Presented) The polymer composition of claim 1, wherein the sacrificial polymer includes polynorbornene.
- 6. (Previously Presented) The polymer composition of claim 3, wherein the polynorbornene includes alkenyl-substituted norbornene.
- 7. (Previously Presented) The polymer composition of claim 1, wherein the photoinitiator is a free radical generators.

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8. (Previously Presented) The polymer composition of claim 3, wherein the photoinitiator is selected from, bis(2.4.6-trimethylbenzoyl)-phenylphosphineoxide, 2-benzyl-2-dimethylamino-l-(4-morpholinophenyl)-butanone-l, 2,2-dimethoxy-l,2-diphenylethan-lone, 2-methyl-1[4-(methylthio)- phenyl]-2-morpholinopropan-l-one, 2-methyl-4'-(methylthio)-2-morpholino-propiophenone, benzoin ethyl ether, and 2,2'-dimethoxy-2-phenyl-acetophenone, and combinations thereof.

- 9. (Previously Presented) The polymer_composition of claim 1, wherein the photoinitiator is selected from, bis(2,4,6-trimethylbenzoyl)-phenylphosphineoxide and 2-benzyl-2-dimethylamino-1 -(4-morpholinophenyl)-butanone-l.
- 10. (Previously Presented) The polymer composition of claim 1, wherein the sacrificial polymer is about 1 to 30% by weight percent of the photodefinable polymer, wherein the photoinitiator is from about 0.5 to 5% by weight of the photodefinable polymer, wherein the polymer composition further comprises a solvent, wherein the solvent is about 65% to 99% by weight percent of the photodefinable polymer.
- 11. (Previously Presented) A method for fabricating a structure, comprising:

disposing a photodefinable polymer composition onto a surface, wherein the photodefinable polymer includes a sacrificial polymer and a photoinitiator selected from a negative tone photoinitiator and a positive tone photoinitiator;

disposing a gray scale photomask onto the photodefinable polymer, wherein the gray scale photomask encodes an optical density profile defining a three-dimensional structure to be formed from the photodefinable polymer;

exposing the photodefinable polymer through the gray scale photomask to optical energy; and

removing portions of the photodefinable polymer to form the three-dimensional structure of cross-linked photodefinable polymer.

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12. (Previously Presented) The method of claim 11, wherein removing includes:

removing unexposed portions of the photodefinable polymer composition to form the three-dimensional structure.

- 13. (Previously Presented) The method of claim 11, wherein removing includes:
 removing exposed portions of the photodefinable polymer composition to form the three-dimensional structure.
- 14. (Previously Presented) The method of claim 11, further comprising: disposing an overcoat layer onto the three-dimensional structure; and decomposing the photodefinable polymer composition, thermally, to form a threedimensional air-region.
- 15. (Original) The method of claim 14, wherein decomposing includes:
 maintaining a constant rate of decomposition as a function of time.
- 16. (Original) The method of claim 14, wherein decomposing includes:

 maintaining a constant rate of mass loss of the photodefinable polymer.
- 17. (Original) The method of claim 14, wherein decomposing includes:

 heating the structure according to the thermal decomposition profile expression

$$T = \frac{E_a}{R} \left[\ln \frac{A(1-rt)^n}{r} \right]^{-1}$$

where R is the universal gas constant, t is time, n is the overall order of decomposition reaction, r the desired polymer decomposition rate, A is the Arrhenius pre-exponential factor, and E_a is the activation energy of the decomposition reaction.

18. (Original) The method of claim 11, wherein the three-dimensional structure has a spatially-varying height.

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19. (Original) A structure, comprising the three-dimensional structure formed using the method of claim 11.

- 20. (Original) A structure, comprising the three-dimensional air-region formed using the method of claim 14.
- 21. (Original) A structure, comprising the three-dimensional air-region formed using the method of claim 15.
- 22. (Original) A structure, comprising the three-dimensional air-region formed using the method of claim 17.
- 23. (Original) A method of decomposing a polymer, comprising:

providing a structure having a substrate, an overcoat layer, and a polymer in a defined area within the overcoat layer;

maintaining a constant rate of decomposition as a function of time; removing the polymer from the area to form an air-region in the defined area.

24. (Original) The method of claim 23, wherein maintaining includes:

heating the structure according to the thermal decomposition profile expression

$$T = \frac{E_a}{R} \left[\ln \frac{A(1-rt)^n}{r} \right]^{-1}$$

where R is the universal gas constant, t is time, n is the overall order of decomposition reaction, r the desired polymer decomposition rate, A is the Arrhenius pre-exponential factor, and E_a is the activation energy of the decomposition reaction.

25. (Original) A structure, comprising:

a substrate;

an air-region area having a spatially-varying height; and an overcoat layer disposed onto a portion of the substrate and engaging a substantial portion of the air-region area.

- 26. (Original) The structure of claim 25, wherein the air-region area has a non-rectangular cross-section.
- 27. (Original) The structure of claim 25, wherein the air-region area has an asymmetrical cross-section.